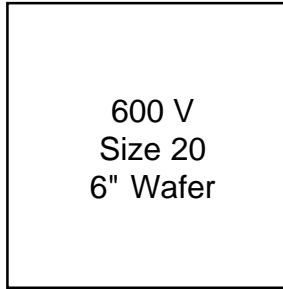


## Hexfred Die in Wafer Form



### Electrical Characteristics ( Wafer Form )

| Parameter | Description               | Guaranteed (Min/Max) | Test Conditions                     |
|-----------|---------------------------|----------------------|-------------------------------------|
| $V_{FM}$  | Forward Voltage           | 1.7V Max.            | $T_J = 25^{\circ}C, I_F = 12.0A$    |
| $BV_R$    | Reverse Breakdown Voltage | 600V Min.            | $T_J = 25^{\circ}C, I_R = 200\mu A$ |
| $I_{RM}$  | Reverse Leakage Current   | 10 $\mu A$ Max.      | $T_J = 25^{\circ}C, V_R = 600V$     |

### Mechanical Data

|  |  |
|--|--|
| Nominal Back Metal Composition, Thickness  | Cr-Ni-Ag ( 1kA-4kA-6kA )   |
| Nominal Front Metal Composition, Thickness | 99% Al, 1% Si (3 microns)  |
| Chip Dimensions                            | 0.085" x 0.164"  |
| Wafer Diameter                             | 150mm, with std. < 100 > flat  |
| Wafer Thickness                            | .015" $\pm$ .003"  |
| Relevant Die Mechanical Dwg. Number        | 01-5160  |
| Minimum Street Width                       | 100 Microns  |
| Reject Ink Dot Size                        | 0.25mm Diameter Minimum  |
| Recommended Storage Environment:           | Store in original container, in dessicated nitrogen, with no contamination |

Reference Standard IR packaged part ( for design ) : IRGBC30MD2

### Die Outline

